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(54) Title: POLISHING AGENT AND METHOD FOR PRODUCING PLANAR LAYERS

(54) Bezeichnung: POLIERMITTEL UND VERFAHREN ZUR HERSTELLUNG PLANARER SCHICHTEN

(57) Abstract: Slurries containing SiO2 are used as a polishing agent for planarizing silicon dioxide layers. It was found that slurries have a higher abrasion rate during the polishing of SiO2 layers if the silica sols used have a bimodal particle size distribution.

(57) Zusammenfassung: Als Poliermittel für das Planarisieren von Siliciumdioxid-Schichten werden SiO_2-haltige Slurries eingesetzt. Es wurde gefunden, dass die Slurries beim Polieren von SiO_2-Schichten eine höhere Abtragsrate besitzen, wenn die eingesetzten Kieselsole eine bimodale Teilchengrößenverteilung aufweisen.